

REMARKS

In view of the above amendments and the following remarks, reconsideration of the rejections contained in the Office Action of August 22, 2008 is respectfully requested.

By this Amendment, claims 25, 27, 30, 33, 36, 50, 55, 64, 66 and 68 have been amended, and claims 35, 37, 56, 65 and 70 have been cancelled. Thus, claims 9-15, 23-34, 36, 38-55, 57-64, 66-69 and 71 are currently pending in the application. No new matter has been added by these amendments.

On pages 5-6 of the Office Action, the Examiner rejected claims 9-15 and 23-71 under the judicially created doctrine of obviousness-type double patenting as being unpatentable over the following: claims 1-43 of Mori et al. (U.S. 6,602,396) (hereinafter Mori '396) in view of Nogami et al. (U.S. 6,693,036); claims 1-11 of Mori et al. (U.S. 6,368,493) (hereinafter Mori '493) in view of Nogami; claims 1-42 of Mori et al. (U.S. 6,875,335) (hereinafter Mori '335) in view of Nogami; and claims 1-18 of Mori et al. (U.S. 6,743,349) (hereinafter Mori '349) in view of Nogami. For the reasons discussed below, it is respectfully submitted that the present claims are clearly patentable over the prior art of record.

Independent claim 9 recites an electrolytic processing apparatus comprising an electrode member, said electrode member comprising an electrode and an ion exchanger covering a surface of the electrode, *wherein a contact width restriction section is provided in said electrode member for restricting a substantial contact width between a workpiece and such a portion of the ion exchanger as usable in processing to a constant width* when the workpiece is brought into contact with the ion exchanger of said electrode member to a certain extent of pressing or higher.

On pages 5-6 of the Office Action, the Examiner indicates that claims of each of Mori '396, Mori '493, Mori '335 and Mori '349 recite all of the features of claim 9 except the claimed relative movement. In this regard, it is noted that the Examiner does not indicate which specific claims of the Mori references recite the particular features of claim 9. However, it is noted that none of the claims of Mori '396, Mori '493, Mori '335 and Mori '349 recite or suggest *a contact width restriction section provided in said electrode member for restricting a substantial contact width between a workpiece and such a portion of the ion exchanger as usable in processing to a constant width*, as required by independent claim 9.

Further, it is noted that Nogami does not disclose or suggest *a contact width restriction section provided in said electrode member for restricting a substantial contact width between a workpiece and such a portion of the ion exchanger as usable in processing to a constant width*, as required by independent claim 9.

Therefore, as a contact width restriction section provided in said electrode member for restricting a substantial contact width between a workpiece and such a portion of the ion exchanger as usable in processing to a constant width, as recited in independent claim 9, is neither disclosed by Nogami nor recited in any of the claims of Mori '396, Mori '493, Mori '335 and Mori '349, it is respectfully submitted that the invention of independent claim 9 is not disclosed or rendered obvious by any of the claims of Mori '396, Mori '493, Mori '335 and Mori '349, or by Nogami, taken either individually or in combination. Accordingly, it is respectfully submitted that the Examiner's double patenting rejection is not applicable to independent claim 9.

Independent claim 23 recites an electrolytic processing method for electrolytically processing a surface of a workpiece, comprising bringing the workpiece into contact with a processing electrode, the processing electrode having an ion exchanger disposed on a surface of the processing electrode and having a narrower width than the workpiece. Further, claim 23 recites *processing the surface of the workpiece while allowing the processing electrode and the workpiece to make a relative movement, wherein a substantial contact width between the workpiece and such a portion of the ion exchanger as used in processing is kept constant during the processing*.

On pages 5-6 of the Office Action, the Examiner indicates that claims of each of Mori '396, Mori '493, Mori '335 and Mori '349 recite all of the features of claim 23 except the claimed relative movement. In this regard, it is noted that the Examiner does not indicate which specific claims of the Mori references recite the particular features of claim 23. However, it is noted that none of the claims of Mori '396, Mori '493, Mori '335 and Mori '349 recite or suggest *processing the surface of the workpiece while allowing the processing electrode and the workpiece to make a relative movement, wherein a substantial contact width between the workpiece and such a portion of the ion exchanger as used in processing is kept constant during*

the processing, as required by independent claim 23.

Further, it is noted that Nogami does not disclose or suggest *processing the surface of the workpiece while allowing the processing electrode and the workpiece to make a relative movement, wherein a substantial contact width between the workpiece and such a portion of the ion exchanger as used in processing is kept constant during the processing*, as required by independent claim 23.

Therefore, as processing the surface of the workpiece while allowing the processing electrode and the workpiece to make a relative movement, wherein a substantial contact width between the workpiece and such a portion of the ion exchanger as used in processing is kept constant during the processing, as recited in independent claim 23, is neither disclosed by Nogami nor recited in any of the claims of Mori '396, Mori '493, Mori '335 and Mori '349, it is respectfully submitted that the invention of independent claim 23 is not disclosed or rendered obvious by any of the claims of Mori '396, Mori '493, Mori '335 and Mori '349, or by Nogami, taken either individually or in combination. Accordingly, it is respectfully submitted that the Examiner's double patenting rejection is not applicable to independent claim 23.

Amended independent claim 25 recites an electrolytic processing method, comprising bringing a workpiece close to or into contact with a processing electrode having an ion exchanger covering a surface of an electrode, applying a voltage between the processing electrode and a feeding electrode that feeds electricity to the workpiece, and supplying a fluid between the workpiece and at least one of the processing electrode and the feeding electrode. Further, claim 25 recites *processing a surface of the workpiece while allowing the processing electrode and the workpiece to make a first relative movement, which is a relative reciprocating movement in a first direction, and, at the same time, allowing the workpiece and the processing electrode to make a second relative movement, which is a relative movement in the first direction for a distance corresponding to an integral multiple of a pitch as determined in a processing amount distribution of the workpiece in the first direction, obtained in the first relative movement.*

On pages 5-6 of the Office Action, the Examiner indicates that claims of each of Mori '396, Mori '493, Mori '335 and Mori '349 recite all of the features of claim 25 except the claimed relative movement. In this regard, it is noted that the Examiner does not indicate which

specific claims of the Mori references recite the particular features of claim 25. However, it is noted that none of the claims of Mori '396, Mori '493, Mori '335 and Mori '349 recite or suggest *processing a surface of the workpiece while allowing the processing electrode and the workpiece to make a first relative movement, which is a relative reciprocating movement in a first direction, and, at the same time, allowing the workpiece and the processing electrode to make a second relative movement, which is a relative movement in the first direction for a distance corresponding to an integral multiple of a pitch as determined in a processing amount distribution of the workpiece in the first direction, obtained in the first relative movement, as required by independent claim 25.*

Further, it is noted that Nogami does not disclose or suggest processing a surface of the workpiece while allowing the processing electrode and the workpiece to make a first relative movement, which is a relative reciprocating movement in a first direction, and, at the same time, allowing the workpiece and the processing electrode to make a second relative movement, which is a relative movement in the first direction for a distance corresponding to an integral multiple of a pitch as determined in a processing amount distribution of the workpiece in the first direction, obtained in the first relative movement, as required by independent claim 25.

Therefore, as processing a surface of the workpiece while allowing the processing electrode and the workpiece to make a first relative movement, which is a relative reciprocating movement in a first direction, and, at the same time, allowing the workpiece and the processing electrode to make a second relative movement, which is a relative movement in the first direction for a distance corresponding to an integral multiple of a pitch as determined in a processing amount distribution of the workpiece in the first direction, obtained in the first relative movement, as recited in independent claim 25, is neither disclosed by Nogami nor recited in any of the claims of Mori '396, Mori '493, Mori '335 and Mori '349, it is respectfully submitted that the invention of independent claim 25 is not disclosed or rendered obvious by any of the claims of Mori '396, Mori '493, Mori '335 and Mori '349, or by Nogami, taken either individually or in combination. Accordingly, it is respectfully submitted that the Examiner's double patenting rejection is not applicable to independent claim 25.

Amended independent claim 33 recites an electrolytic processing method, comprising

bringing a workpiece close to or into contact with a processing electrode having an ion exchanger covering a surface of an electrode, applying a voltage between the processing electrode and a feeding electrode that feeds electricity to the workpiece, and supplying a fluid between the workpiece and at least one of the processing electrode and the feeding electrode. Further, claim 33 recites *processing a surface of the workpiece while allowing the processing electrode and the workpiece to make a first relative movement and, at the same time, allowing the workpiece and the processing electrode to make a second relative movement in a first direction, wherein the second relative movement is repeated, and a moving direction of the workpiece in the second relative movement is changed by rotating the workpiece through a predetermined rotational angle.*

On pages 5-6 of the Office Action, the Examiner indicates that claims of each of Mori '396, Mori '493, Mori '335 and Mori '349 recite all of the features of claim 33 except the claimed relative movement. In this regard, it is noted that the Examiner does not indicate which specific claims of the Mori references recite the particular features of claim 33. However, it is noted that none of the claims of Mori '396, Mori '493, Mori '335 and Mori '349 recite or suggest *processing a surface of the workpiece while allowing the processing electrode and the workpiece to make a first relative movement and, at the same time, allowing the workpiece and the processing electrode to make a second relative movement in a first direction, wherein the second relative movement is repeated, and a moving direction of the workpiece in the second relative movement is changed by rotating the workpiece through a predetermined rotational angle*, as required by independent claim 33.

Further, it is noted that Nogami does not disclose or suggest *processing a surface of the workpiece while allowing the processing electrode and the workpiece to make a first relative movement and, at the same time, allowing the workpiece and the processing electrode to make a second relative movement in a first direction, wherein the second relative movement is repeated, and a moving direction of the workpiece in the second relative movement is changed by rotating the workpiece through a predetermined rotational angle*, as required by independent claim 33.

Therefore, as processing a surface of the workpiece while allowing the processing electrode and the workpiece to make a first relative movement and, at the same time, allowing

the workpiece and the processing electrode to make a second relative movement in a first direction, wherein the second relative movement is repeated, and a moving direction of the workpiece in the second relative movement is changed by rotating the workpiece through a predetermined rotational angle, as recited in independent claim 33, is neither disclosed by Nogami nor recited in any of the claims of Mori '396, Mori '493, Mori '335 and Mori '349, it is respectfully submitted that the invention of independent claim 33 is not disclosed or rendered obvious by any of the claims of Mori '396, Mori '493, Mori '335 and Mori '349, or by Nogami, taken either individually or in combination. Accordingly, it is respectfully submitted that the Examiner's double patenting rejection is not applicable to independent claim 33.

Independent claim 41 recites an electrolytic processing apparatus, comprising a processing electrode that can come close to or into contact with a workpiece, a feeding electrode for feeding electricity to the workpiece, a holder for holding the workpiece and bringing the workpiece close to or into contact with the processing electrode, *a plurality of ion exchangers disposed between the workpiece and at least one of the processing electrode and the feeding electrode, and a feed mechanism for feeding and changing at least one ion exchanger of the plurality of ion exchangers.*

On pages 5-6 of the Office Action, the Examiner indicates that claims of each of Mori '396, Mori '493, Mori '335 and Mori '349 recite all of the features of claim 41 except the claimed relative movement. In this regard, it is noted that the Examiner does not indicate which specific claims of the Mori references recite the particular features of claim 41. However, it is noted that none of the claims of Mori '396, Mori '493, Mori '335 and Mori '349 recite or suggest an electrolytic processing apparatus which includes *a plurality of ion exchangers disposed between the workpiece and at least one of the processing electrode and the feeding electrode, and a feed mechanism for feeding and changing at least one ion exchanger of the plurality of ion exchangers*, as required by independent claim 41.

Further, it is noted that Nogami does not disclose or suggest an electrolytic processing apparatus which includes *a plurality of ion exchangers disposed between the workpiece and at least one of the processing electrode and the feeding electrode, and a feed mechanism for feeding and changing at least one ion exchanger of the plurality of ion exchangers*, as required by

independent claim 41.

Therefore, as a plurality of ion exchangers disposed between the workpiece and at least one of the processing electrode and the feeding electrode, and a feed mechanism for feeding and changing at least one ion exchanger of the plurality of ion exchangers, as recited in independent claim 41, are neither disclosed by Nogami nor recited in any of the claims of Mori '396, Mori '493, Mori '335 and Mori '349, it is respectfully submitted that the invention of independent claim 41 is not disclosed or rendered obvious by any of the claims of Mori '396, Mori '493, Mori '335 and Mori '349, or by Nogami, taken either individually or in combination. Accordingly, it is respectfully submitted that the Examiner's double patenting rejection is not applicable to independent claim 41.

Amended independent claim 50 recites an electrolytic processing apparatus, comprising a processing electrode that can come close to or into contact with a workpiece, a feeding electrode for feeding electricity to the workpiece, a holder for holding the workpiece and bringing the workpiece close to or into contact with the processing electrode, *an ion exchanger disposed between the workpiece and at least one of the processing electrode and the feeding electrode, a water-permeable member superimposed on a surface of the ion exchanger, and feed mechanisms for feeding and changing the ion exchanger and the water-permeable member, respectively.*

On pages 5-6 of the Office Action, the Examiner indicates that claims of each of Mori '396, Mori '493, Mori '335 and Mori '349 recite all of the features of claim 50 except the claimed relative movement. In this regard, it is noted that the Examiner does not indicate which specific claims of the Mori references recite the particular features of claim 50. However, it is noted that none of the claims of Mori '396, Mori '493, Mori '335 and Mori '349 recite or suggest an electrolytic processing apparatus which includes *an ion exchanger disposed between the workpiece and at least one of the processing electrode and the feeding electrode, a water-permeable member superimposed on a surface of the ion exchanger, and feed mechanisms for feeding and changing the ion exchanger and the water-permeable member, respectively*, as required by independent claim 50.

Further, it is noted that Nogami does not disclose or suggest an electrolytic processing apparatus which includes *an ion exchanger disposed between the workpiece and at least one of*

the processing electrode and the feeding electrode, a water-permeable member superimposed on a surface of the ion exchanger, and feed mechanisms for feeding and changing the ion exchanger and the water-permeable member, respectively, as required by independent claim 50.

Therefore, as an ion exchanger disposed between the workpiece and at least one of the processing electrode and the feeding electrode, a water-permeable member superimposed on a surface of the ion exchanger, and feed mechanisms for feeding and changing the ion exchanger and the water-permeable member, respectively, as recited in independent claim 50, are neither disclosed by Nogami nor recited in any of the claims of Mori '396, Mori '493, Mori '335 and Mori '349, it is respectfully submitted that the invention of independent claim 50 is not disclosed or rendered obvious by any of the claims of Mori '396, Mori '493, Mori '335 and Mori '349, or by Nogami, taken either individually or in combination. Accordingly, it is respectfully submitted that the Examiner's double patenting rejection is not applicable to independent claim 50.

Amended independent claim 55 recites an electrolytic processing apparatus, comprising a processing electrode that can come close to or into contact with a workpiece, a feeding electrode for feeding electricity to the workpiece, a holder for holding the workpiece and bringing the workpiece close to or into contact with the processing electrode, and an ion exchanger disposed between the workpiece and at least one of the processing electrode and the feeding electrode, *wherein the processing electrode or the feeding electrode is comprised of a plurality of electrodes, and the respective electrodes can move close to or apart from the workpiece independently.*

On pages 5-6 of the Office Action, the Examiner indicates that claims of each of Mori '396, Mori '493, Mori '335 and Mori '349 recite all of the features of claim 55 except the claimed relative movement. In this regard, it is noted that the Examiner does not indicate which specific claims of the Mori references recite the particular features of claim 55. However, it is noted that none of the claims of Mori '396, Mori '493, Mori '335 and Mori '349 recite or suggest an electrolytic processing apparatus in which *the processing electrode or the feeding electrode is comprised of a plurality of electrodes, and the respective electrodes can move close to or apart from the workpiece independently, as required by independent claim 55.*

Further, it is noted that Nogami does not disclose or suggest an electrolytic processing

apparatus in which *the processing electrode or the feeding electrode is comprised of a plurality of electrodes, and the respective electrodes can move close to or apart from the workpiece independently*, as required by independent claim 55.

Therefore, as an electrolytic processing apparatus in which the processing electrode or the feeding electrode is comprised of a plurality of electrodes, and the respective electrodes can move close to or apart from the workpiece independently, as recited in independent claim 55, is neither disclosed by Nogami nor recited in any of the claims of Mori '396, Mori '493, Mori '335 and Mori '349, it is respectfully submitted that the invention of independent claim 55 is not disclosed or rendered obvious by any of the claims of Mori '396, Mori '493, Mori '335 and Mori '349, or by Nogami, taken either individually or in combination. Accordingly, it is respectfully submitted that the Examiner's double patenting rejection is not applicable to independent claim 55.

Independent claim 57 recites a substrate holder for holding a substrate and bringing the substrate into contact with a processing electrode to carry out electrolytic processing of the substrate, comprising a flange portion connected to a shaft, and *a chucking member which can move with respect to the flange portion in an axial direction of the shaft and which holds the substrate*.

On pages 5-6 of the Office Action, the Examiner indicates that claims of each of Mori '396, Mori '493, Mori '335 and Mori '349 recite all of the features of claim 57 except the claimed relative movement. In this regard, it is noted that the Examiner does not indicate which specific claims of the Mori references recite the particular features of claim 57. However, it is noted that none of the claims of Mori '396, Mori '493, Mori '335 and Mori '349 recite or suggest a substrate holder which includes a flange portion connected to a shaft, and *a chucking member which can move with respect to the flange portion in an axial direction of the shaft and which holds the substrate*, as required by independent claim 57.

Further, it is noted that Nogami discloses an X-axis movement mechanism 41 having a wafer table 42 and a holder 45 for rotatably holding the wafer. However, Nogami does not disclose or suggest a substrate holder which includes a flange portion connected to a shaft, and a chucking member which can move with respect to the flange portion in an axial direction of the

shaft and which holds the substrate, as required by independent claim 57.

Therefore, as a substrate holder which includes a flange portion connected to a shaft, and a chucking member which can move with respect to the flange portion in an axial direction of the shaft and which holds the substrate, as recited in independent claim 57, is neither disclosed by Nogami nor recited in any of the claims of Mori '396, Mori '493, Mori '335 and Mori '349, it is respectfully submitted that the invention of independent claim 57 is not disclosed or rendered obvious by any of the claims of Mori '396, Mori '493, Mori '335 and Mori '349, or by Nogami, taken either individually or in combination. Accordingly, it is respectfully submitted that the Examiner's double patenting rejection is not applicable to independent claim 57.

Independent claim 64 recites an electrolytic processing apparatus, comprising a processing electrode, a feeding electrode for feeding electricity to a substrate, a substrate holder for holding the substrate and bringing the substrate into contact with the processing electrode, an ion exchanger disposed between the substrate held by the substrate holder and at least one of the processing electrode and the feeding electrode, a power source for applying a voltage between the processing electrode and the feeding electrode, and a drive section for allowing the substrate held by the substrate holder and the processing electrode to make a relative movement. Further, claim 64 recites that the substrate holder is a substrate holder for holding the substrate and bringing the substrate into contact with the processing electrode to carry out electrolytic processing of the substrate, and includes *a flange portion connected to a shaft, and a chucking member which can move with respect to the flange portion in an axial direction of the shaft and which holds the substrate.*

On pages 5-6 of the Office Action, the Examiner indicates that claims of each of Mori '396, Mori '493, Mori '335 and Mori '349 recite all of the features of claim 64 except the claimed relative movement. In this regard, it is noted that the Examiner does not indicate which specific claims of the Mori references recite the particular features of claim 64. However, as indicated above, it is noted that none of the claims of Mori '396, Mori '493, Mori '335 and Mori '349 recite or suggest a substrate holder which includes a flange portion connected to a shaft, and *a chucking member which can move with respect to the flange portion in an axial direction of the shaft and which holds the substrate*, as required by independent claim 64.

Further, as also indicate above, Nogami does not disclose or suggest a substrate holder which includes a flange portion connected to a shaft, and a chucking member which can move with respect to the flange portion in an axial direction of the shaft and which holds the substrate, as required by independent claim 64.

Therefore, as a substrate holder which includes a flange portion connected to a shaft, and a chucking member which can move with respect to the flange portion in an axial direction of the shaft and which holds the substrate, as recited in independent claim 64, is neither disclosed by Nogami nor recited in any of the claims of Mori '396, Mori '493, Mori '335 and Mori '349, it is respectfully submitted that the invention of independent claim 64 is not disclosed or rendered obvious by any of the claims of Mori '396, Mori '493, Mori '335 and Mori '349, or by Nogami, taken either individually or in combination. Accordingly, it is respectfully submitted that the Examiner's double patenting rejection is not applicable to independent claim 64.

Amended independent claim 68 recites an electrolytic processing method, comprising providing a processing electrode and a feeding electrode, applying a voltage between the processing electrode and the feeding electrode, *holding a substrate by a substrate holder, the substrate holder including a flange portion connected to a shaft and a chucking member for holding the substrate*, disposing an ion exchanger between the substrate and at least one of the processing electrode and the feeding electrode, and allowing the substrate to be in contact with the processing electrode while allowing the substrate and the processing electrode to make a relative movement, thereby processing the surface of the substrate.

On pages 5-6 of the Office Action, the Examiner indicates that claims of each of Mori '396, Mori '493, Mori '335 and Mori '349 recite all of the features of claim 68 except the claimed relative movement. In this regard, it is noted that the Examiner does not indicate which specific claims of the Mori references recite the particular features of claim 68. However, it is noted that none of the claims of Mori '396, Mori '493, Mori '335 and Mori '349 recite or suggest *holding a substrate by a substrate holder, the substrate holder including a flange portion connected to a shaft and a chucking member for holding the substrate*, as required by independent claim 68.

Further, Nogami does not disclose or suggest *holding a substrate by a substrate holder*,

the substrate holder including a flange portion connected to a shaft and a chucking member for holding the substrate, as required by independent claim 68.

Therefore, as holding a substrate by a substrate holder, the substrate holder including a flange portion connected to a shaft and a chucking member for holding the substrate, as recited in independent claim 68, is neither disclosed by Nogami nor recited in any of the claims of Mori '396, Mori '493, Mori '335 and Mori '349, it is respectfully submitted that the invention of independent claim 68 is not disclosed or rendered obvious by any of the claims of Mori '396, Mori '493, Mori '335 and Mori '349, or by Nogami, taken either individually or in combination. Accordingly, it is respectfully submitted that the Examiner's double patenting rejection is not applicable to independent claim 68.

In view of the above, it is respectfully submitted that the Examiner's double patenting rejections are inapplicable to any of independent claims 9, 23, 25, 33, 41, 50, 55, 57, 64 and 68.

On pages 2-4 of the Office Action, the Examiner rejected claims 25-26, 28-40, 55, 57-64 and 67-71 under 35 U.S.C. § 102(e) as being anticipated by or, in the alternative, under 35 U.S.C. § 103(a) as being obvious over Nogami. For the reasons discussed below, it is respectfully submitted that the present claims are patentable over Nogami.

As indicated above, independent claim 25 recites an electrolytic processing method which includes *processing a surface of the workpiece while allowing the processing electrode and the workpiece to make a first relative movement, which is a relative reciprocating movement in a first direction, and, at the same time, allowing the workpiece and the processing electrode to make a second relative movement, which is a relative movement in the first direction for a distance corresponding to an integral multiple of a pitch as determined in a processing amount distribution of the workpiece in the first direction, obtained in the first relative movement.*

On pages 3-4 of the Office Action, the Examiner indicates that Nogami discloses that a polishing tool and a polishing object move relatively along a predetermined plane while being rotated, as set forth in column 3, lines 61-63. However, as discussed above, it is noted that Nogami does not disclose or suggest processing a surface of the workpiece while allowing the processing electrode and the workpiece to make a first relative movement, which is a relative

reciprocating movement in a first direction, and, at the same time, allowing the workpiece and the processing electrode to make a second relative movement, which is a relative movement in the first direction for a distance corresponding to an integral multiple of a pitch as determined in a processing amount distribution of the workpiece in the first direction, obtained in the first relative movement, as required by independent claim 25.

Further, it is noted that amended claim 25 recites bringing a workpiece close to or into contact with a processing electrode *having an ion exchanger covering a surface of an electrode*, which was a feature of previous claim 27. It is noted that claim 27 was not rejected as being anticipated by or, in the alternative, as being obvious over Nogami.

Therefore, as bringing a workpiece close to or into contact with a processing electrode having an ion exchanger covering a surface of an electrode, and processing a surface of the workpiece while allowing the processing electrode and the workpiece to make a first relative movement, which is a relative reciprocating movement in a first direction, and, at the same time, allowing the workpiece and the processing electrode to make a second relative movement, which is a relative movement in the first direction for a distance corresponding to an integral multiple of a pitch as determined in a processing amount distribution of the workpiece in the first direction, obtained in the first relative movement, as recited in independent claim 25, is not disclosed or suggested by Nogami, it is respectfully submitted that the invention of independent claim 25 is not anticipated by or rendered obvious by Nogami.

As discussed above, amended independent claim 33 recites an electrolytic processing method which includes *processing a surface of the workpiece while allowing the processing electrode and the workpiece to make a first relative movement and, at the same time, allowing the workpiece and the processing electrode to make a second relative movement in a first direction, wherein the second relative movement is repeated, and a moving direction of the workpiece in the second relative movement is changed by rotating the workpiece through a predetermined rotational angle*.

On pages 3-4 of the Office Action, the Examiner indicates that Nogami discloses that a polishing tool and a polishing object move relatively along a predetermined plane while being rotated, as set forth in column 3, lines 61-63. However, as discussed above, it is noted that

Nogami does not disclose or suggest *processing a surface of the workpiece while allowing the processing electrode and the workpiece to make a first relative movement and, at the same time, allowing the workpiece and the processing electrode to make a second relative movement in a first direction, wherein the second relative movement is repeated, and a moving direction of the workpiece in the second relative movement is changed by rotating the workpiece through a predetermined rotational angle*, as required by independent claim 33.

Further, it is noted that amended claim 33 recites bringing a workpiece close to or into contact with a processing electrode *having an ion exchanger covering a surface of an electrode*, which was a feature of previous claim 27. It is noted that claim 27 was not rejected as being anticipated by or, in the alternative, as being obvious over Nogami.

Therefore, as bringing a workpiece close to or into contact with a processing electrode having an ion exchanger covering a surface of an electrode, and processing a surface of the workpiece while allowing the processing electrode and the workpiece to make a first relative movement and, at the same time, allowing the workpiece and the processing electrode to make a second relative movement in a first direction, wherein the second relative movement is repeated, and a moving direction of the workpiece in the second relative movement is changed by rotating the workpiece through a predetermined rotational angle, as recited in independent claim 33, is not disclosed or suggested by Nogami, it is respectfully submitted that the invention of independent claim 33 is not anticipated by or rendered obvious by Nogami.

As indicated above, amended independent claim 55 recites an electrolytic processing apparatus in which *the processing electrode or the feeding electrode is comprised of a plurality of electrodes, and the respective electrodes can move close to or apart from the workpiece independently*.

In this regard, as also indicated above, it is noted that Nogami does not disclose or suggest an electrolytic processing apparatus in which *the processing electrode or the feeding electrode is comprised of a plurality of electrodes, and the respective electrodes can move close to or apart from the workpiece independently*, as required by independent claim 55.

Further, it is noted that amended claim 55 recites *an ion exchanger disposed between the workpiece and at least one of the processing electrode and the feeding electrode*, which was a

feature of previous claim 56. It is noted that claim 56 was not rejected as being anticipated by or, in the alternative, as being obvious over Nogami.

Therefore, as an electrolytic processing apparatus in which the processing electrode or the feeding electrode is comprised of a plurality of electrodes, and the respective electrodes can move close to or apart from the workpiece independently, as recited in independent claim 55, is not disclosed or suggested by Nogami, it is respectfully submitted that the invention of independent claim 55 is not anticipated by or rendered obvious by Nogami.

As also discussed above, independent claim 57 recites a substrate holder for holding a substrate and bringing the substrate into contact with a processing electrode to carry out electrolytic processing of the substrate, comprising a flange portion connected to a shaft, and *a chucking member which can move with respect to the flange portion in an axial direction of the shaft and which holds the substrate.*

As indicated above, it is noted that Nogami discloses an X-axis movement mechanism 41 having a wafer table 42 and a holder 45 for rotatably holding the wafer. However, Nogami does not disclose or suggest a substrate holder which includes a flange portion connected to a shaft, and a chucking member which can move with respect to the flange portion in an axial direction of the shaft and which holds the substrate, as required by independent claim 57.

Therefore, as a substrate holder which includes a flange portion connected to a shaft, and a chucking member which can move with respect to the flange portion in an axial direction of the shaft and which holds the substrate, as recited in independent claim 57, is not disclosed or suggested by Nogami, it is respectfully submitted that the invention of independent claim 57 is not anticipated by or rendered obvious by Nogami.

As also noted above, independent claim 64 recites an electrolytic processing apparatus having a substrate holder which includes *a flange portion connected to a shaft, and a chucking member which can move with respect to the flange portion in an axial direction of the shaft and which holds the substrate.*

Further, as also indicate above, Nogami does not disclose or suggest a substrate holder which includes a flange portion connected to a shaft, and a chucking member which can move with respect to the flange portion in an axial direction of the shaft and which holds the substrate,

as required by independent claim 64.

In addition, it is noted that amended claim 64 recites *an ion exchanger disposed between the substrate held by the substrate holder and at least one of the processing electrode and the feeding electrode*, which was a feature of previous claim 65. It is noted that claim 65 was not rejected as being anticipated by or, in the alternative, as being obvious over Nogami.

Therefore, as an ion exchanger disposed between the substrate held by the substrate holder and at least one of the processing electrode and the feeding electrode, and a substrate holder which includes a flange portion connected to a shaft, and a chucking member which can move with respect to the flange portion in an axial direction of the shaft and which holds the substrate, as recited in independent claim 64, is not disclosed or suggested by Nogami, it is respectfully submitted that the invention of independent claim 64 is not anticipated by or rendered obvious by Nogami.

Therefore, it is respectfully submitted that independent claims 9, 23, 25, 33, 41, 50, 55, 57, 64 and 68, as well as claims 10-15, 24, 26-32, 34, 36, 38-40, 42-49, 51-54, 58-63, 66-69 and 71, which depend therefrom, are clearly allowable over the prior art of record.

In view of the foregoing amendments and remarks, it is respectfully submitted that the present application is clearly in condition for allowance. An early notice to that effect is respectfully solicited.

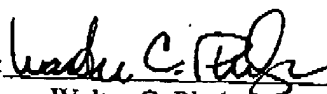
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If, after reviewing this Amendment, the Examiner feels there are any issues remaining which must be resolved before the application can be passed to issue, the Examiner is respectfully requested to contact the undersigned by telephone in order to resolve such issues.

Respectfully submitted,

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January 22, 2009